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	ОТІ	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)													
Fith	Ger	German Office Action dated June 21, 2004 with English translation.													
5th	H. C Sub	H. GOSSNER, et al.; "Self-Organizing Growth of Nanometer Mesa Structures on Silicon (100) Substrates", Jpn. J. Appln. Phys. Vol. 33 (1994) pp. 2268-2271, Part 1, No. 4B, April 1994.													
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